

AMENDMENT TO THE SPECIFICATION

Please replace the pending paragraph beginning on page 6, line 19 with the following paragraph:

An additional characteristic of the phase-change masking material is that the resulting mask should be robust enough to withstand wet-chemical or dry etching processes. When a dry etching process is used, phase change masking materials with low-vapor pressures may be used. Wax is an example of a phase-change material with the previously described characteristics. Kemamide 180-based waxes, a stearyl erucamide material, from Xerox Corporation of Stamford Connecticut, is one example of a suitable wax for use as a phase change material.